



Vapor Phase Decomposition (VPD)

Seehund[®] Series

Vapor Phase Decomposition System (VPD)

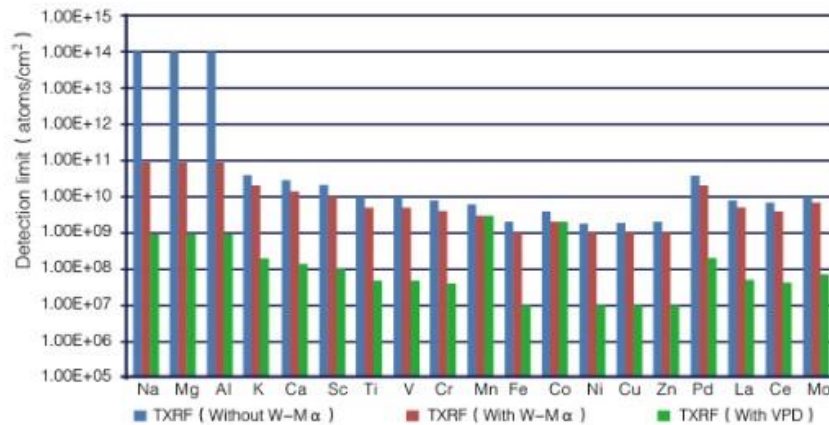


System Features

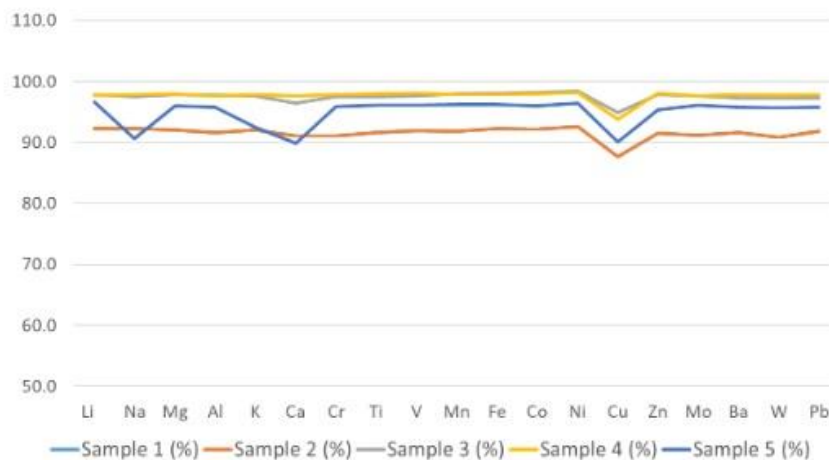
- Compatible with 12" and 8" wafers
- 6" compatible with carrier wafers
- Applicable for metallic contamination monitoring in IC fabrication, wafer manufacturing and wafer reclaim processes
- Used in combination with an inductively coupled plasma mass spectrometer (ICP-MS), or a total reflection X-ray fluorescence spectrometer (TXRF)
- VPD improves the contaminant detection limits for ICP-MS or TXRF by two orders of magnitude. This drastically enhances the detection sensitivity, meeting the needs to monitor and control trace amounts of metal contamination in the above-mentioned industries

Process Data

TXRF Detection Limit Improves Hundredfold with VPD



Element Recovery Rate: VPD & ICP-MS



Overview

The **Seehund® Series** VPD system is a proprietary product developed specifically to monitor surface metallic impurities for IC fabrication, wafer manufacturing, and wafer reclaim. This system uses standard parts widely adopted by 12" and 8" production lines around the **world**. Its design is compliant with SEMI Standards.